

Exercise 6: Electrical properties

1. The electron mobility of an InGaAs layer is $10\,000\text{ cm}^2/\text{Vs}$ at $T = 300\text{ K}$. a) Calculate the drift velocity of the electrons in an electric field of 10 kV/cm , which is a typical field strength in semiconductors. b) The relaxation times of electrons and holes are assumed to be equal. Calculate the mobility of holes when $m_e^* = 0.050 m_0$ and $m_h^* = 0.40 m_0$.
2. Electron mobility in weakly n-type ($n = 1 \times 10^{13}\text{ cm}^{-3}$) GaAs ($m_e^* = 0.067 m_0$) layer is $200\,000\text{ cm}^2/\text{Vs}$ at $T = 77\text{ K}$. a) Calculate the average distance l_e and time τ_e between collisions for thermally moving electron (assuming kinetic energy of $E = 3k_B T/2$ for the electron). b) Calculate the conductivity of the sample at 77 K . The effect of holes to the conductivity can be ignored.
3. For intrinsic semiconductor the relaxation times for phonon scattering and ionised impurity scattering at $T = 300\text{ K}$ are $\tau_L = 1.1\text{ ps}$ and $\tau_I = 1.9\text{ ps}$, respectively. The effective mass of the carriers is $0.10 m_0$. The temperature dependences of the scattering processes are

$$\tau_L \propto T^{-\frac{3}{2}} \quad \wedge \quad \tau_I \propto T^{\frac{3}{2}}.$$
 Other scattering processes can be ignored. a) At what temperature is the mobility largest? b) What is the value of the largest mobility?

4. An n-type InGaAs layer with a thickness of $2.5\text{ }\mu\text{m}$ is grown on a semi-insulating InP wafer. A 1.0 mm wide and 2.0 mm long strip is etched from the layer. The Hall voltage of $V_H = 12\text{ mV}$ is obtained from the layer in Hall measurement with a normal magnetic field of $B_z = 0.50\text{ T}$ when 10 mA current is led through the sample. At the same time voltage difference $V_x = 150\text{ mV}$ is measured between the ends of the strip. Calculate the carrier (electron) density and mobility in the InGaAs layer.

